

In the Specification:

Please replace the paragraph beginning on page 57, line 1, with the following rewritten paragraph:

Like the first embodiment, as indicated by a chain double-dashed line in FIG.25, the dielectric projections 31 are formed in a zig-zag fashion to oppose to positions that pass through between the slits 30a to 30d of the pixel electrode 30. The projections 31 are formed by photosensitive acrylic resin PC-335 (product name manufactured by JSR Inc.), for example. Patterns of the projections 31 are formed by coating the photosensitive acrylic resin on the substrate by virtue of spin coating, then baking the resin at 90 °C for 20 minutes, then irradiating selectively the ultraviolet rays by using a photo mask, then developing the resin by an organic alkaline liquid developer (~~TMAHO, 2 wt%~~)(TMAH, 0.2 wt%), and then baking the resin at 200 °C for 60 minutes. A width of the projection 31 is 10 µm and a height of the projection 31 is 1.5 µm.